Figure 1.

PG = Protecting Group or Polymeric Support

Figure 3. Preparation of Cyclic Substituents via Intra-molecular Dipolar Cycloaddition

Figure 4. Preparation of Cyclic Substituents via Intra-molecular Dipolar Cycloaddition

Figure 5.

R3

R3

R4

R5

PG = Protecting Group or Polymeric Support

R6

FG Q = NH

PG = Protecting Group or Polymeric Support

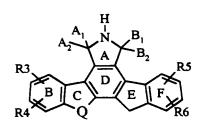
R6

$$A_2$$
 A_1
 A_2
 A_3
 A_4
 A_2
 A_4
 A_4

Figure 9.

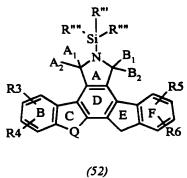
Figure 10.

PG = Protecting Group or Polymeric Support



(47)

TsOH, Toluene, NMP, 140°C ÓН (51a) R' = H, R'' = H(51b) R' = OMe, R'' = Ploymer



- (49) R' = H, R'' = H >> soluble protected FP (N-protecting group abbreviated as DMB)
- $R^{""} = Me, R^{""} = tBu$ (TBS) R"" = Ph, R" = tBu (TPS)
- (50) R' = OMe, R" = Polymer >> solid-bound PG (the resin reagent reffered to as Rink-acid resin) This is reffered to ion the text as "Resin"

(e.g. Polymer = copolystyrene-1%divinylbenzene)

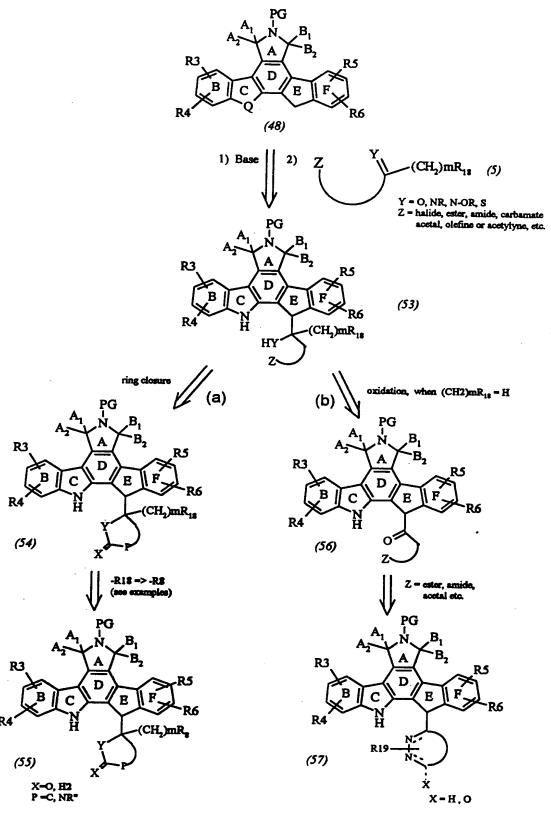


Figure 13. Preparation of Cyclic Substituents via Intra-molecular Dipolar Cycloaddition

Figure 14. Preparation of Cyclic Substituents via Intra-molecular Dipolar Cycloaddition

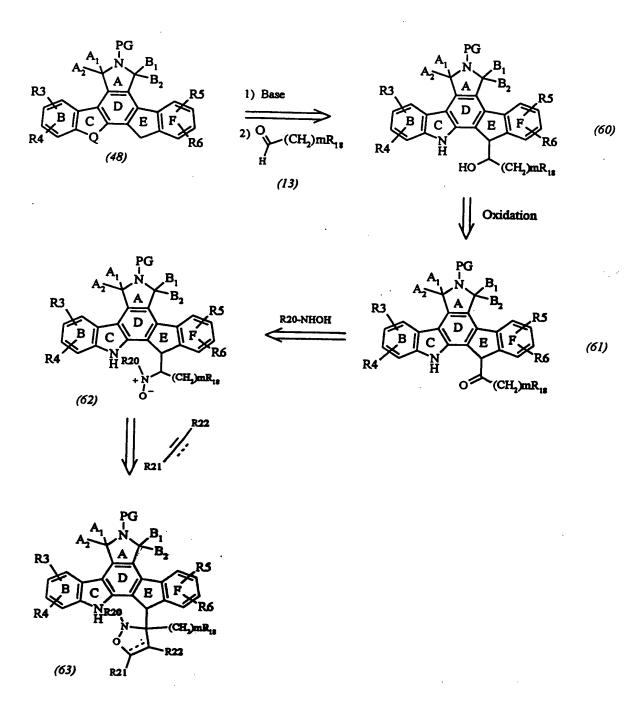


Figure 15.

(76)

(72)

(74)

Figure 18.

Figure 19.

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